fðner's Docket No. 081468-0307475

Reference: P-1797.000-US

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

LUIJKX et al.

Application No.:

10/748,849

Confirmation No.:

2810

Filed:

December 31, 2003

Group No.:

2851

Examiner:

For:

OPTICAL ATTENUATOR DEVICE, RADIATION SYSTEM AND LITHOGRAPHIC

APPARATUS THEREWITH AND DEVICE MANUFACTURING METHOD

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

SUPPLEMENTAL APPLICATION DATA SHEET 37 C.F.R. § 1.76(c)

The following information on the Application Data Sheet is changed as indicated:

BIBLIOGRAPHIC DATA

1. Applicant information is being modified and/or added.

SEVENTH applicant: JOHANNES HENDRIK EVERHARDUS ALDEGONDA MUIJDERMAN

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Residence

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NINTH applicant:

JAN JAAP KRIKKE

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2. Assignee information is being modified.

The assignee(s) of this application is/are:

ASML NETHERLANDS B.V.

De Run 6501, NL-5504 DR Veldhoven, The Netherlands

Extent of interest of assignee in application: ENTIRE RIGHT, TITLE AND INTEREST

Date: July 6, 2004

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